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PATENT

Attorney Docket No.: SLM-05800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Robert W. Corrigan et al.

Serial No.: 09/832,738

Filed: April 10, 2001

For: **METHOD, SYSTEM AND
DISPLAY APPARATUS FOR
ENCRYPTED CINEMA**

) Group Art Unit: 2643

) Examiner:

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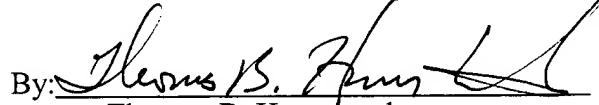
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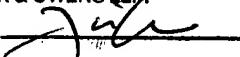
Respectfully submitted,
HAVERSTOCK & OWENS LLP

By: 
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Reg. No.: 32,571

Dated: 7-16-03

Attorneys for Applicants

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United States Patents or Published Patent Applications have been filed electronically (EFS ID # 43669);(EFS ID #43671); (EFS ID #43672); (EFS ID #43673); (EFS ID #43674); (EFS ID #43675); (EFS ID #43677); (EFS ID #43678); (EFS ID #43679); (EFS ID #43680); (EFS ID #43682); (EFS ID #43683); (EFS ID #43686); (EFS ID #43688); (EFS ID #43689); and (EFS ID #43690).

Applicants have become aware of the following printed publication which may be material to the examination of this application:

- U.S. Patent No. Des. 334,557;
- U.S. Patent No. Des. 334,742;
- U.S. Patent No. Des. 337,320;
- U.S. Patent No. Re. 16,767;
- U.S. Patent No. Re. 25,169;
- German Publication No. DE 32 33 195 A1;
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- German Publication No. DE 198 46 532 C1;
- European Publication No. EP 0 089 044 A2;
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- European Publication No. EP 0 654 777 A1;
- European Publication No. EP 0 658 868 A1;
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- European Publication No. EP 0 851 492 A2;
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- Japanese Patent Abstract JP 53-39068;
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- Japanese Patent Abstract JP 61-145838;
- Japanese Patent Abstract JP 63-234767;
- Japanese Patent Abstract JP 63-305323;
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- Japanese Patent Abstract JP 7-281161;
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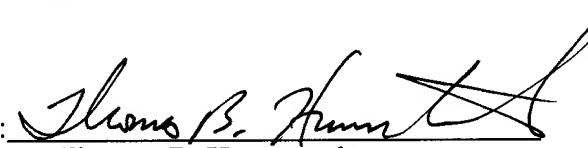
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Respectfully submitted,
HAVERSTOCK & OWENS LLP

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